

Fig. 1

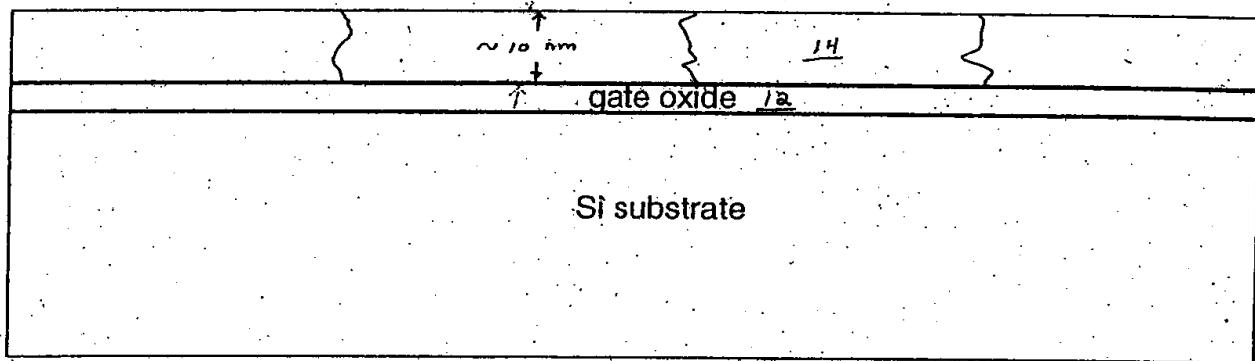


Fig. 2

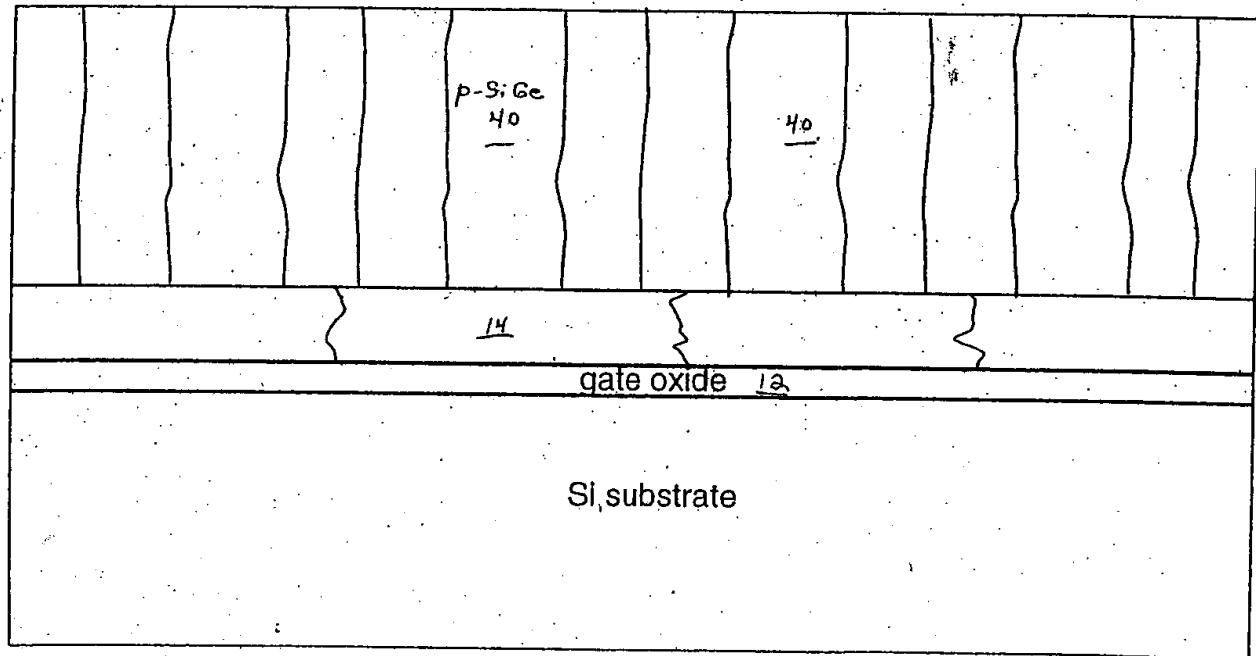


Fig. 3

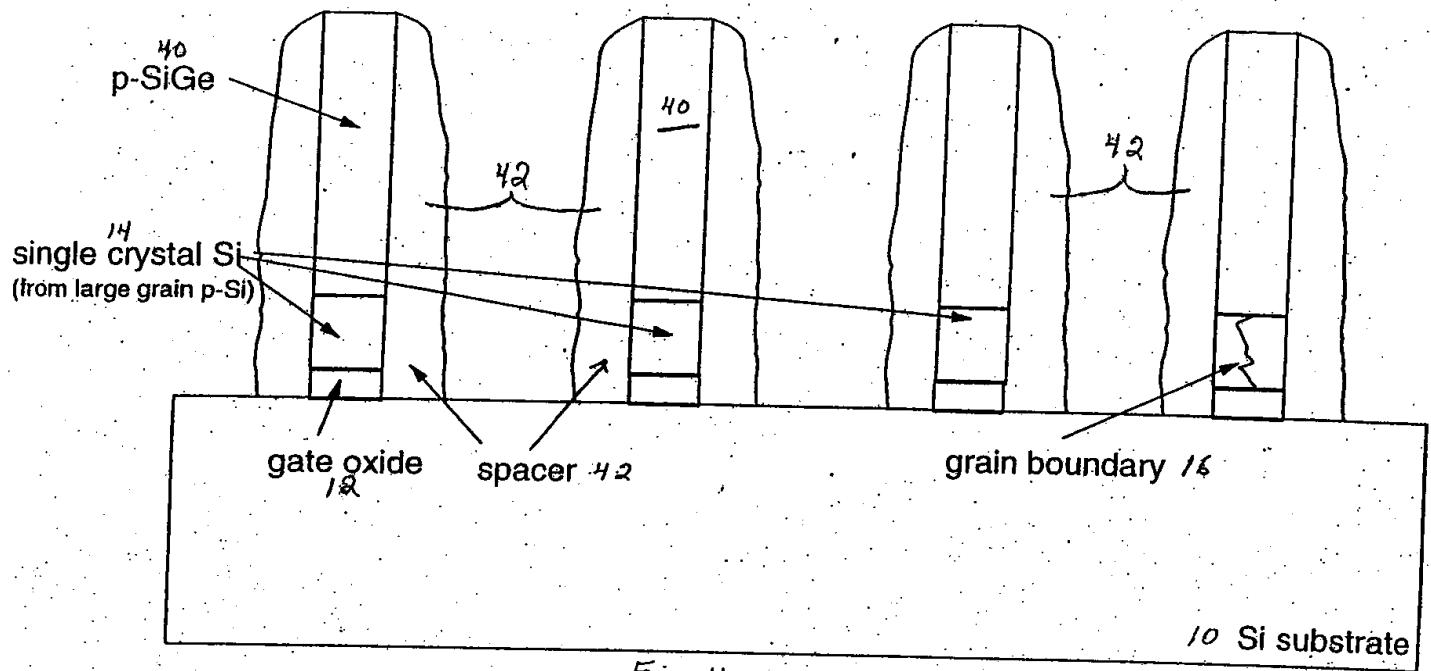


Fig. 4

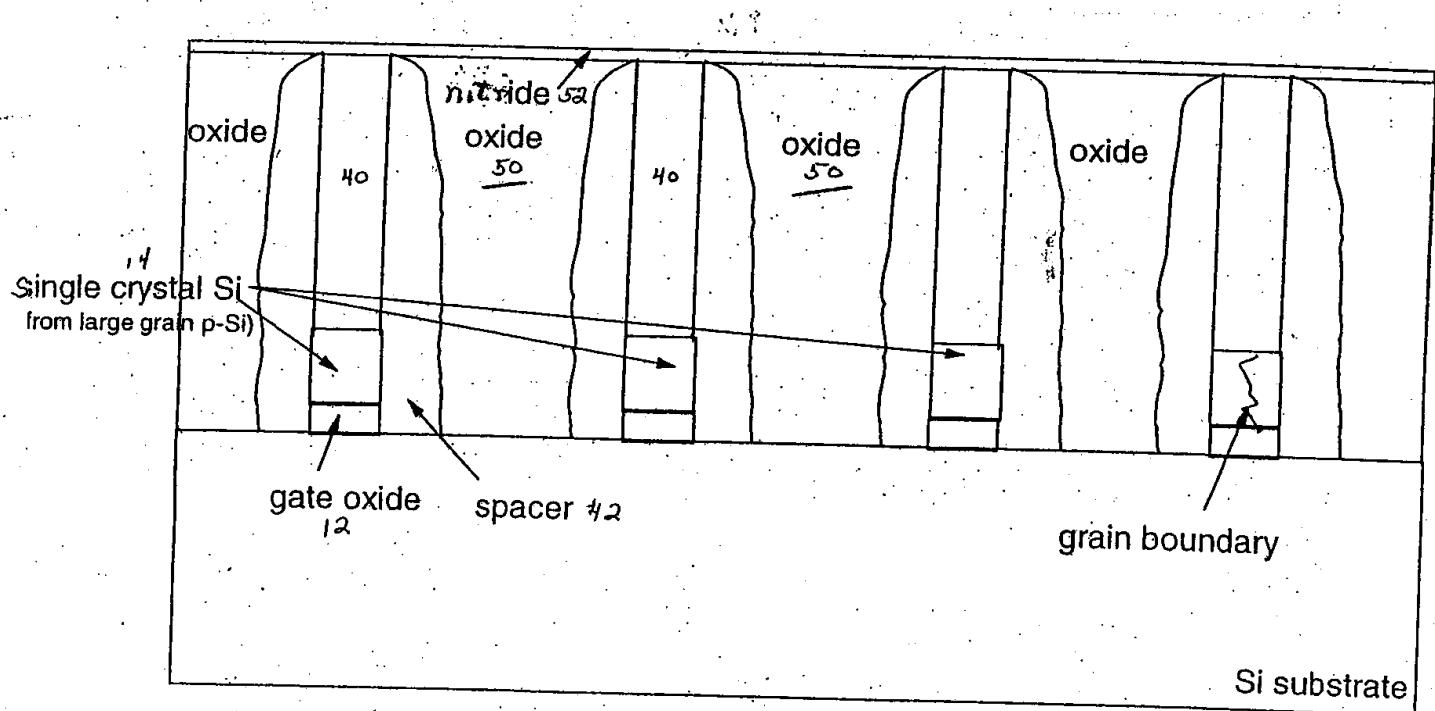


Fig. 5

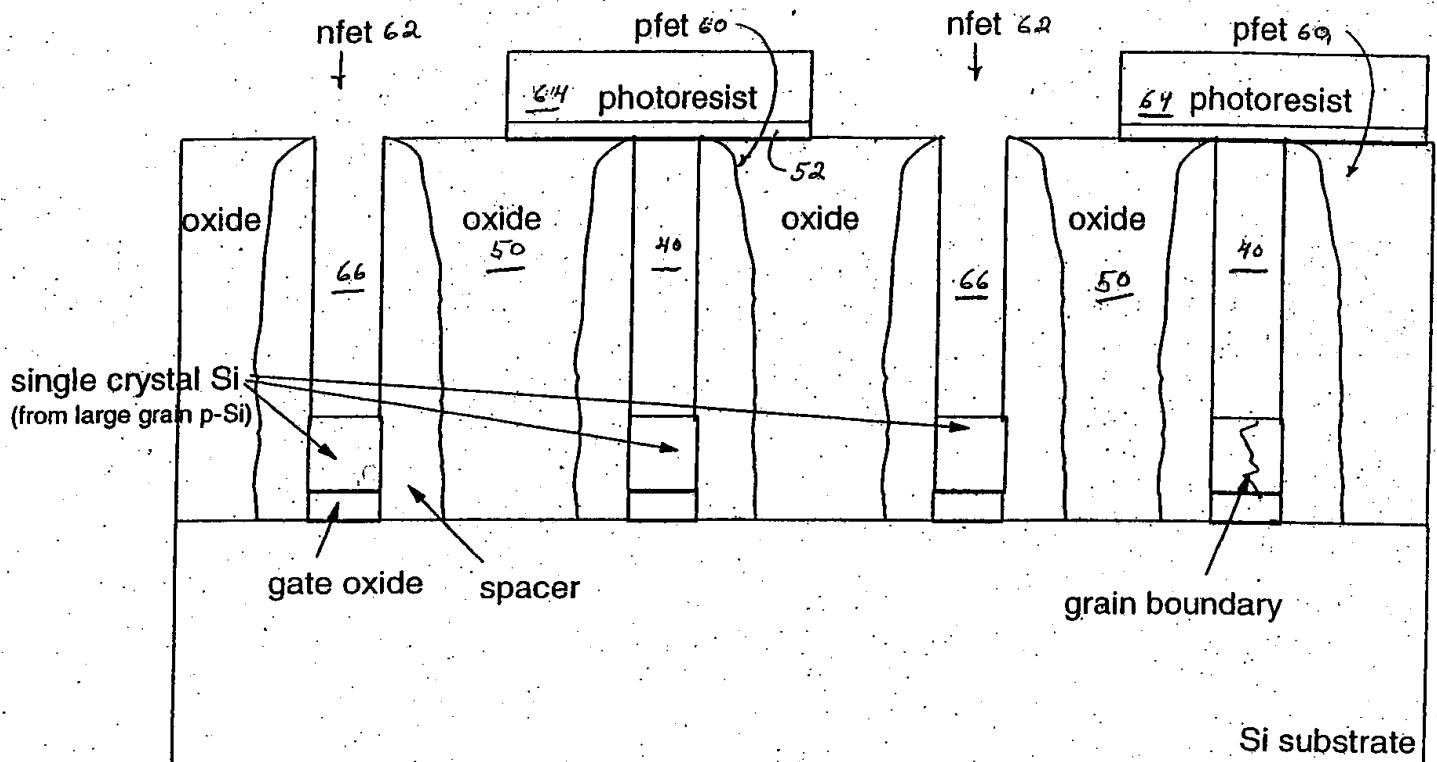


Fig. 6

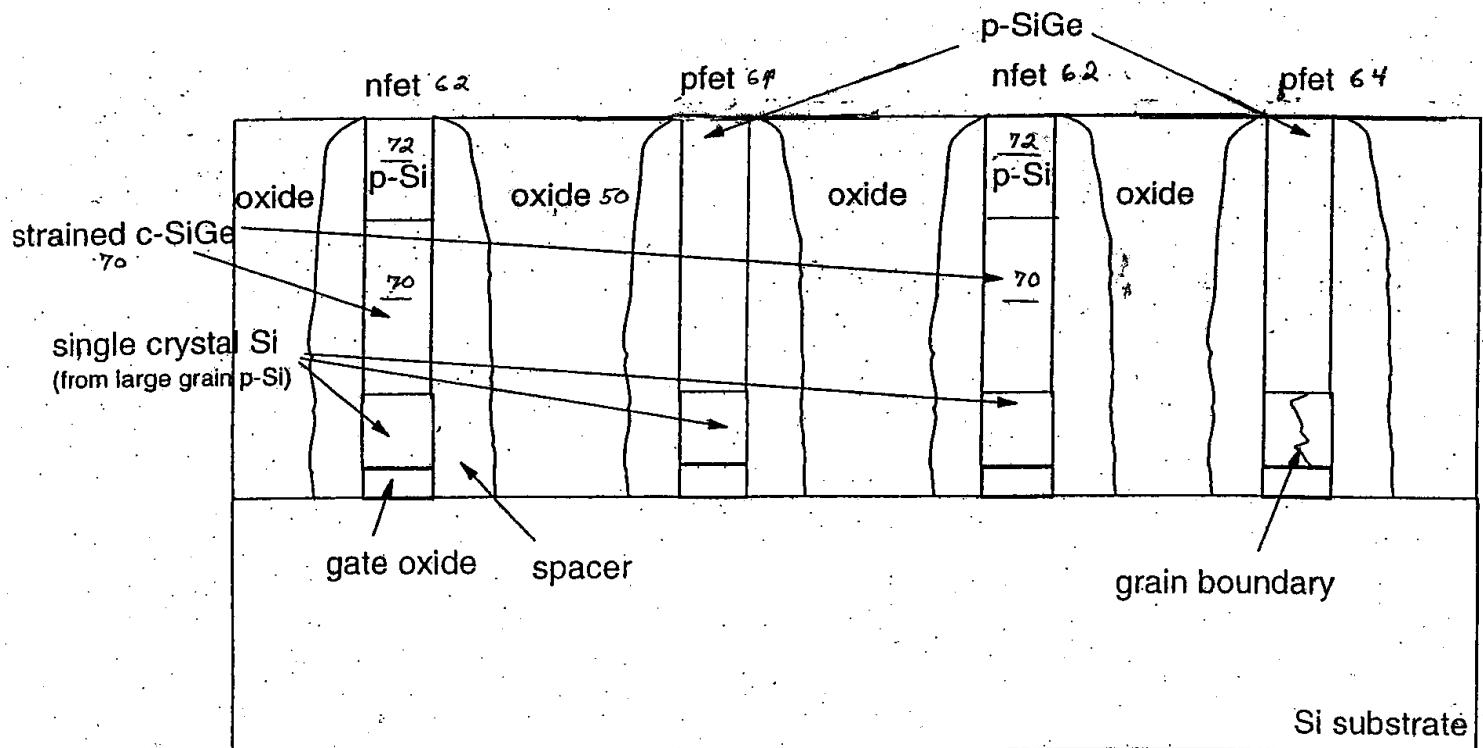


Fig. 7

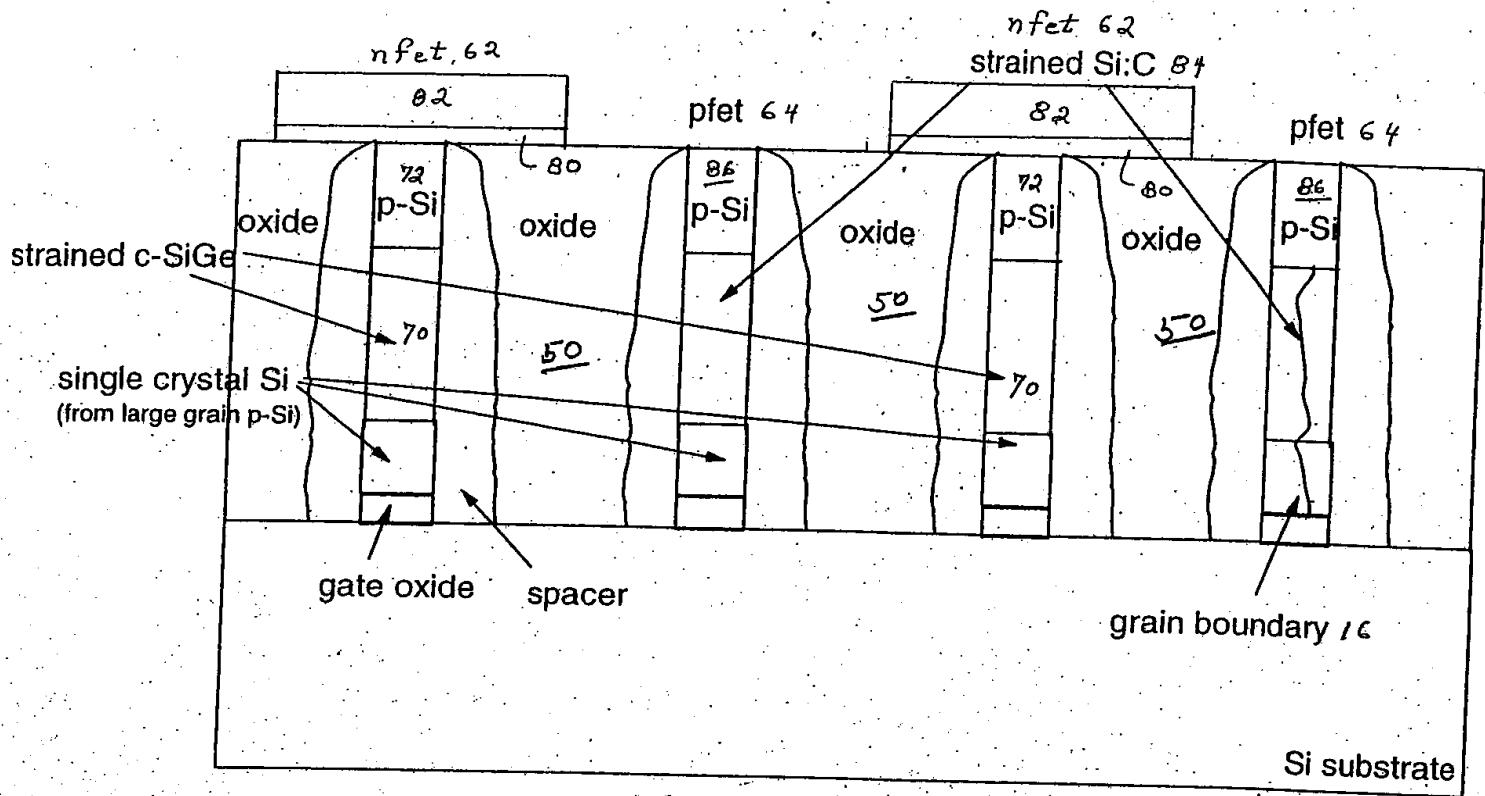


Fig. 8

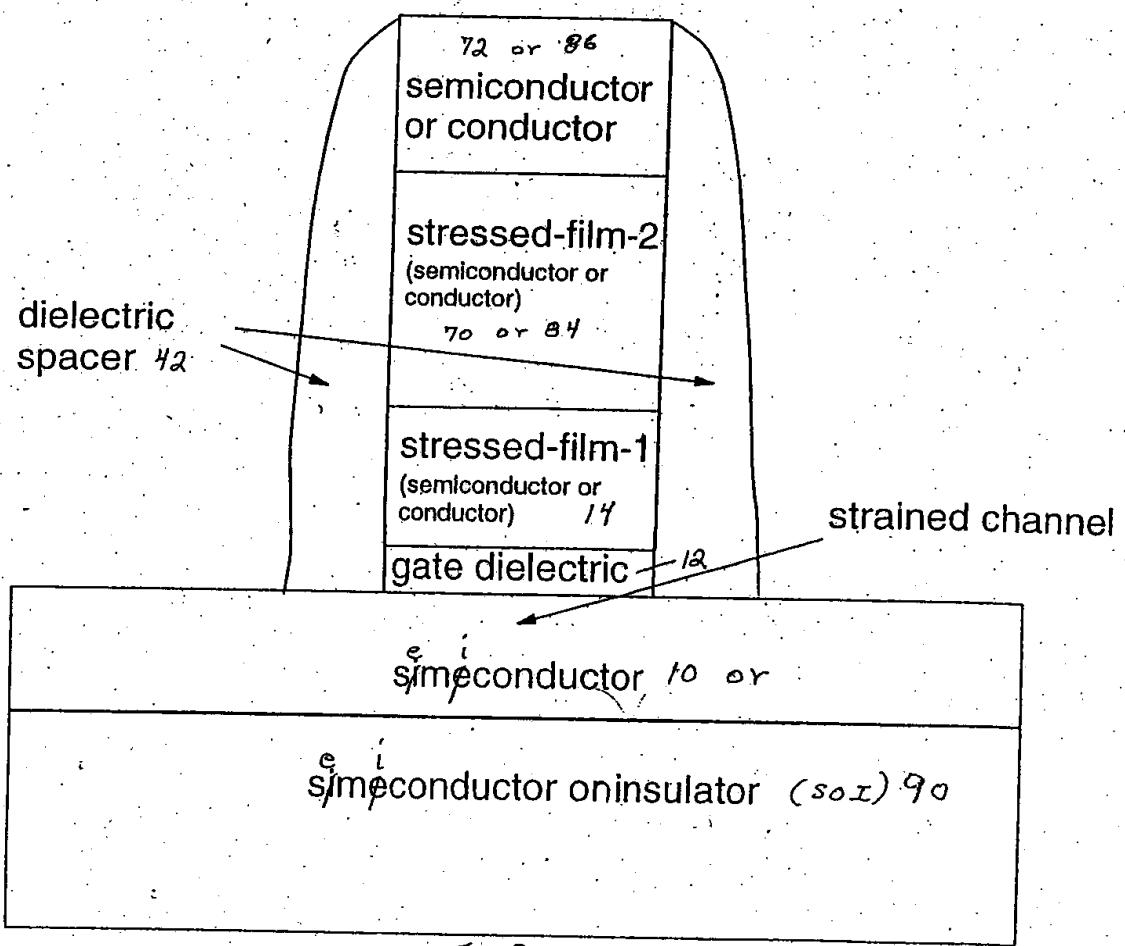


Fig. 9

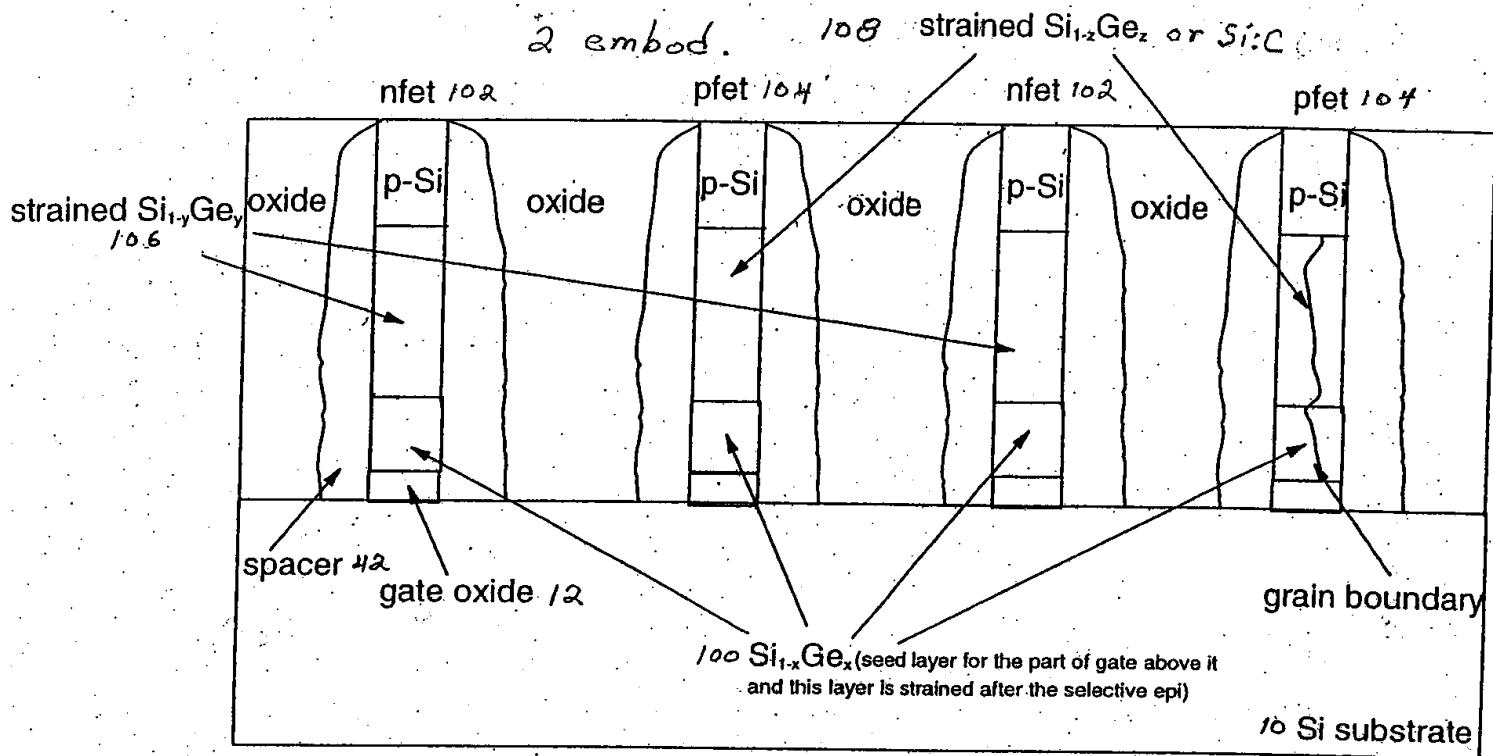


Fig. 10

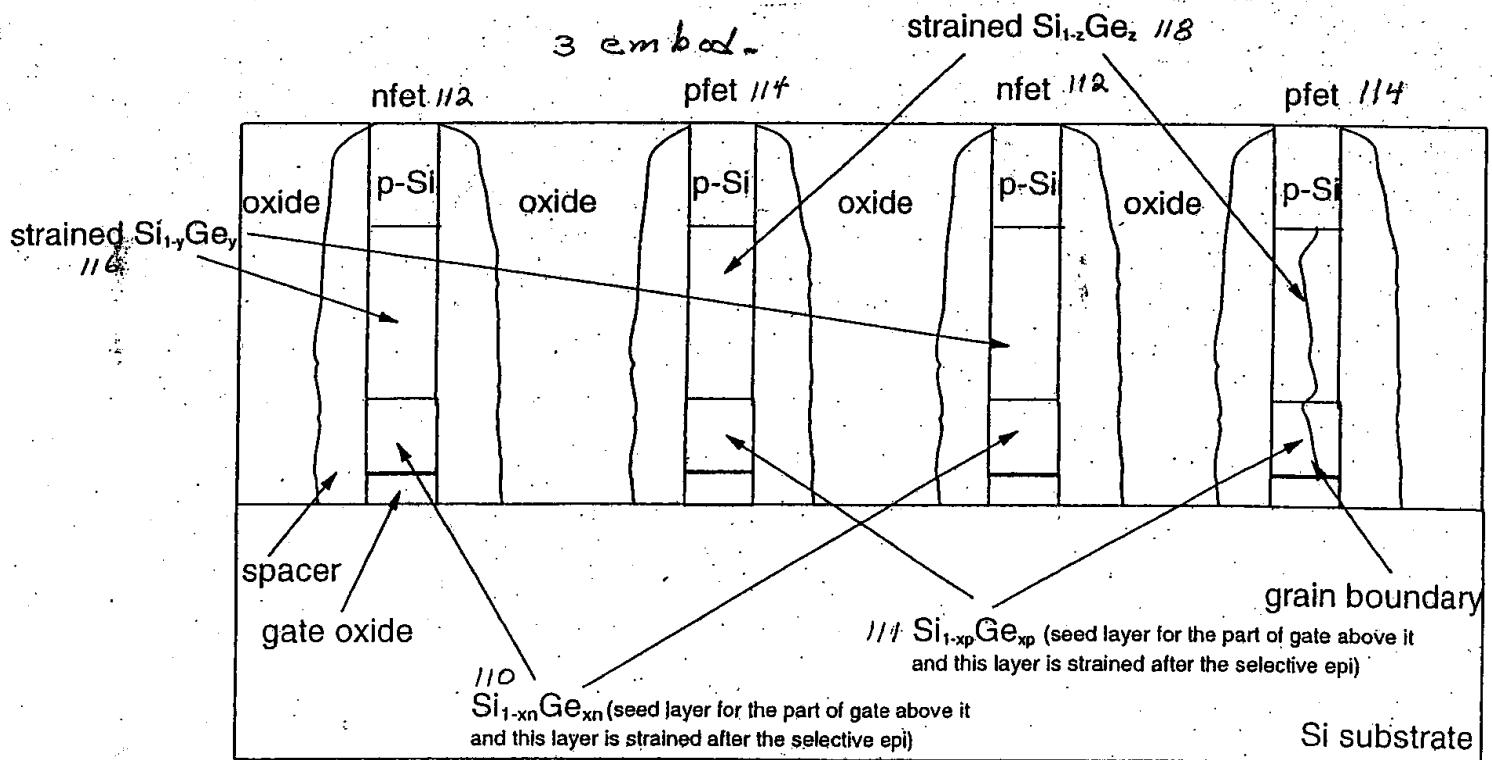


Fig. 11

4 embed
Schematic of layer structure before gate patterning

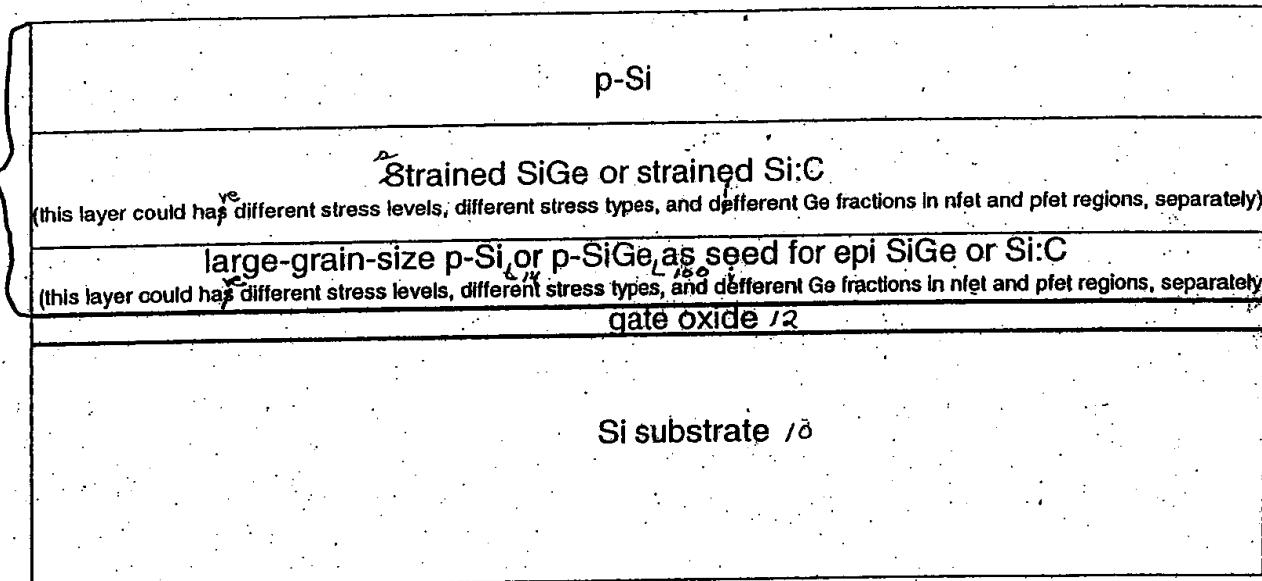


Fig. 12

bonded oxide/Si interface 133

5 embed.

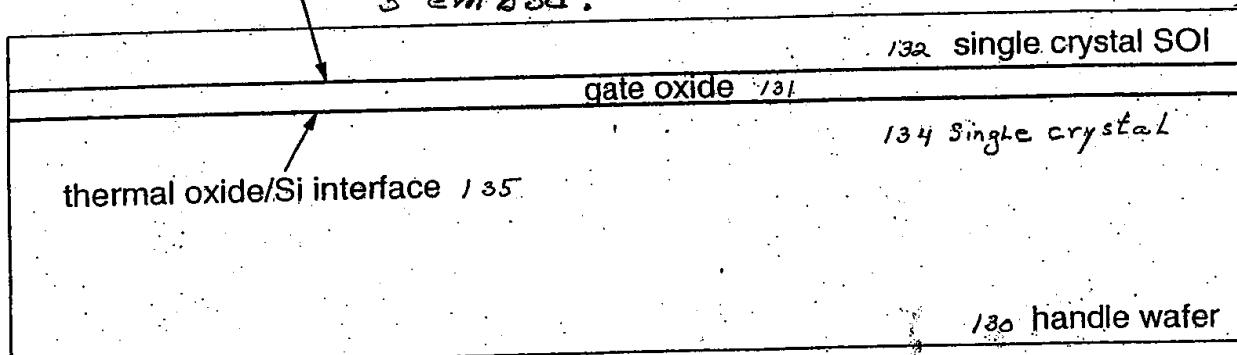


Fig. 13

6 embed

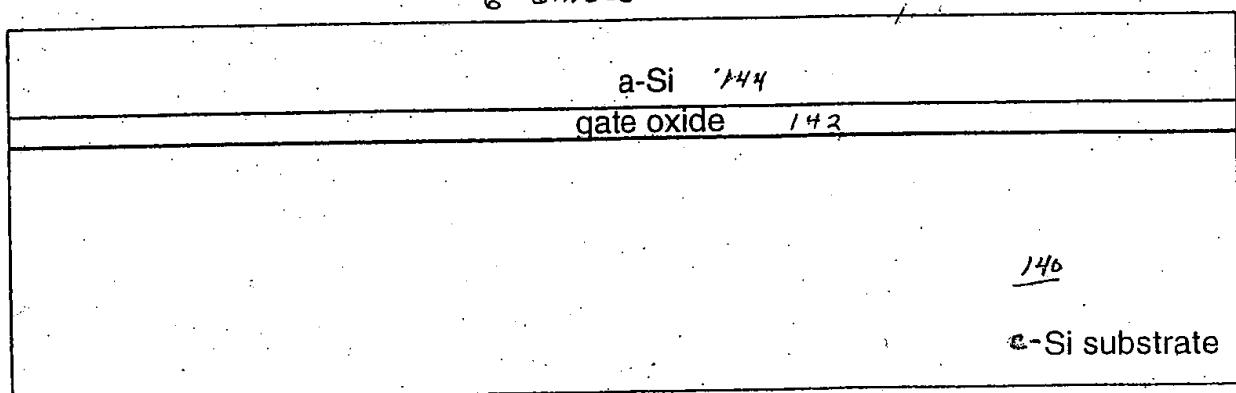


Fig. 14

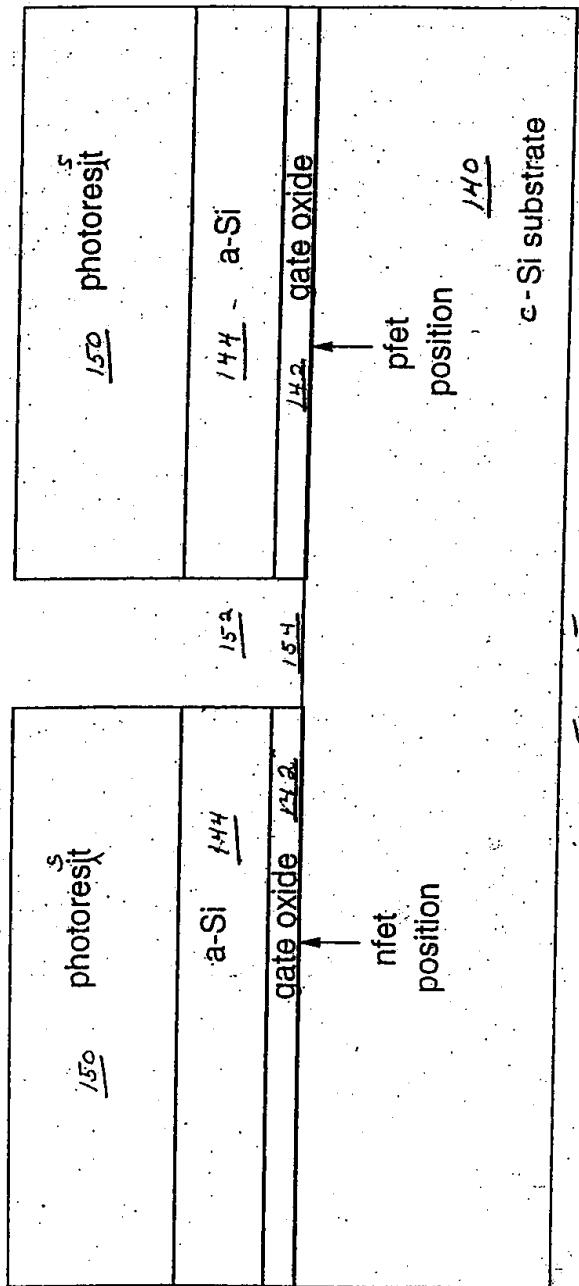


Fig. 15

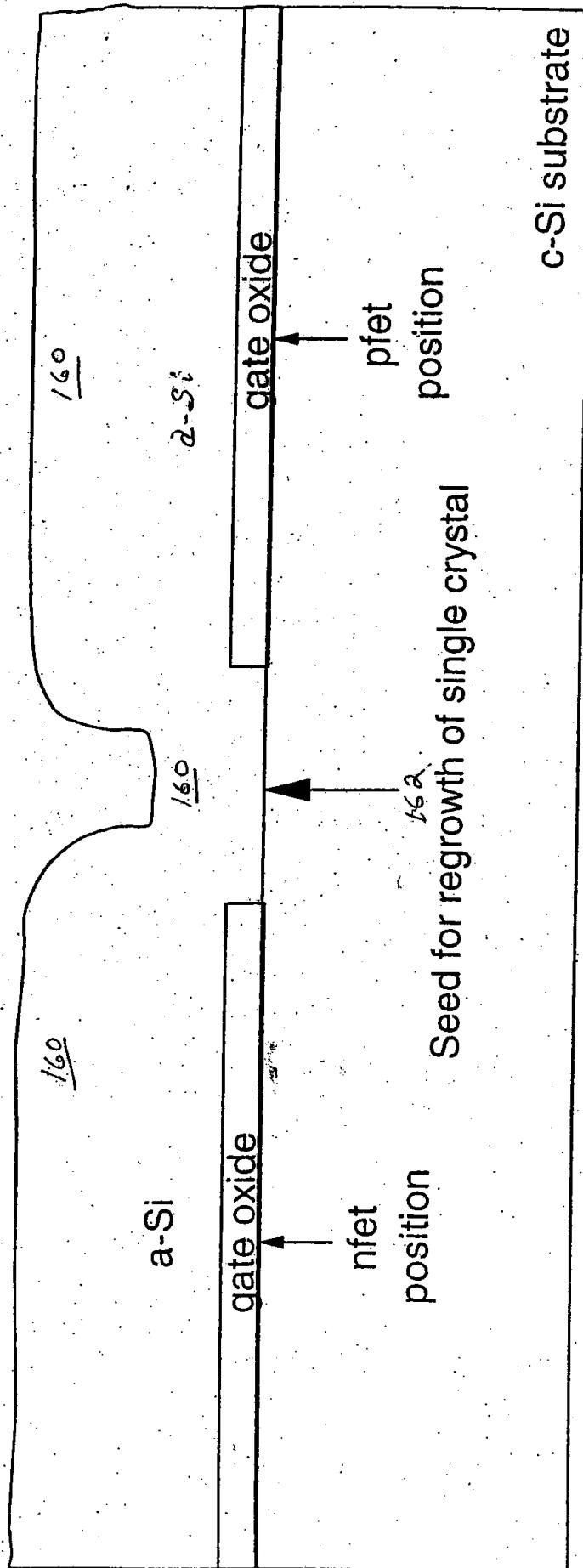


Fig. 16

c-Si substrate

Seed for regrowth of single crystal

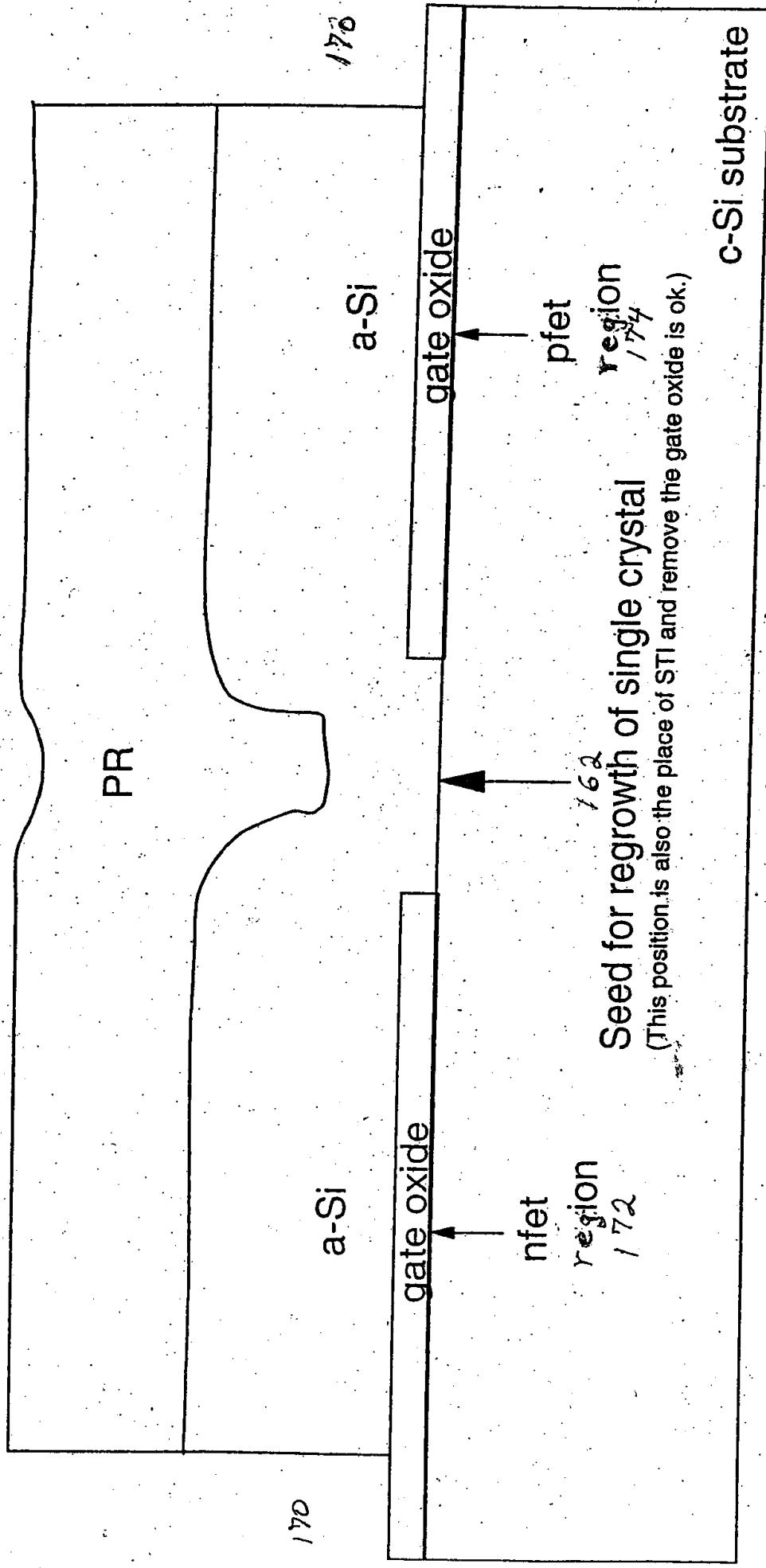


Fig. 17

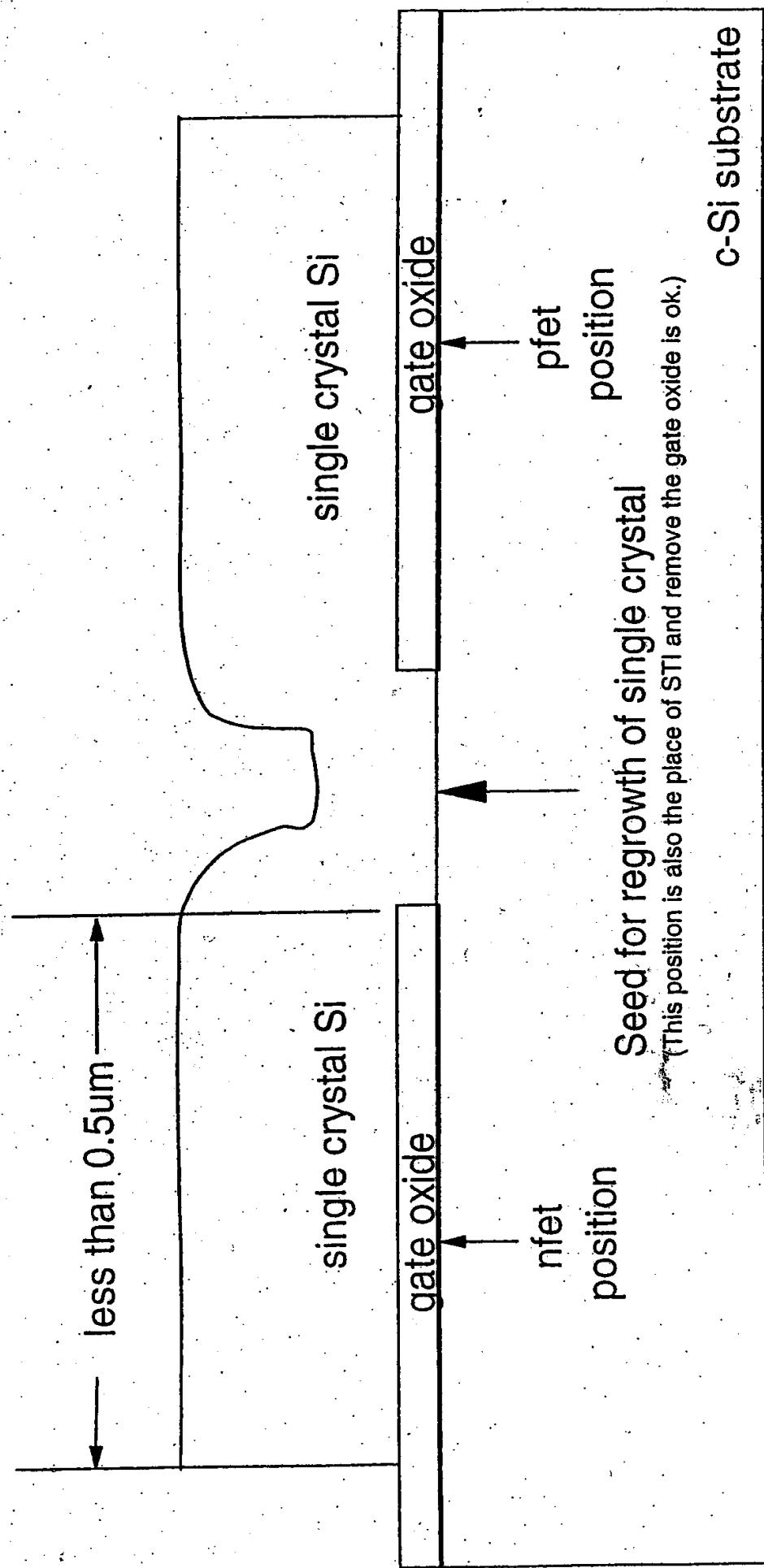


Fig. 18